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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/717,279	7,279 11/19/2003 Steven J. Koester		YOR920030533US1 (17110)	7401	
	7590 07/09/200 FT MURPHY & PRES	EXAMINER			
400 GARDEN		MAI, ANH D			
SUITE 300 GARDEN CITY, NY 11530			ART UNIT	PAPER NUMBER	
			2814		
			MAIL DATE	DELIVERY MODE	
			07/09/2009	PAPER	

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

Advisory Action Before the Filing of an Appeal Brief

Application No.	Applicant(s)	
10/717,279	KOESTER, STEVEN J.	
Examiner	Art Unit	
Anh D. Mai	2814	

	7 till B. Wal	2017
The MAILING DATE of this communication appe	ears on the cover sheet with the	correspondence address
THE REPLY FILED <u>02 June 2009</u> FAILS TO PLACE THIS APF	PLICATION IN CONDITION FOR A	LLOWANCE.
1. The reply was filed after a final rejection, but prior to or on application, applicant must timely file one of the following application in condition for allowance; (2) a Notice of Application (RCE) in compliance with 37 (periods:	replies: (1) an amendment, affidav eal (with appeal fee) in compliance	it, or other evidence, which places the with 37 CFR 41.31; or (3) a Request
a) The period for reply expiresmonths from the mailing	g date of the final rejection.	
b) The period for reply expires on: (1) the mailing date of this A no event, however, will the statutory period for reply expire I Examiner Note: If box 1 is checked, check either box (a) or a state of the checked.	ater than SIX MONTHS from the mailin (b). ONLY CHECK BOX (b) WHEN THE	g date of the final rejection.
MONTHS OF THE FINAL REJECTION. See MPEP 706.07 (Extensions of time may be obtained under 37 CFR 1.136(a). The date have been filed is the date for purposes of determining the period of ex under 37 CFR 1.17(a) is calculated from: (1) the expiration date of the set forth in (b) above, if checked. Any reply received by the Office later may reduce any earned patent term adjustment. See 37 CFR 1.704(b) NOTICE OF APPEAL	on which the petition under 37 CFR 1.1 tension and the corresponding amount shortened statutory period for reply origet than three months after the mailing da	of the fee. The appropriate extension fee inally set in the final Office action; or (2) as
2. ☐ The Notice of Appeal was filed on A brief in comp	bliance with 37 CFR 41 37 must be	filed within two months of the date of
filing the Notice of Appeal (37 CFR 41.37(a)), or any exte Notice of Appeal has been filed, any reply must be filed w AMENDMENTS	nsion thereof (37 CFR 41.37(e)), to	avoid dismissal of the appeal. Since a
 The proposed amendment(s) filed after a final rejection, (a) They raise new issues that would require further co (b) They raise the issue of new matter (see NOTE below 	nsideration and/or search (see NO	
(c) They are not deemed to place the application in being appeal; and/or (d) They present additional claims without canceling a	tter form for appeal by materially re	
NOTE: (See 37 CFR 1.116 and 41.33(a)).		ected claims.
4. The amendments are not in compliance with 37 CFR 1.1		mpliant Amendment (PTOL-324).
5. Applicant's reply has overcome the following rejection(s)		,
 Newly proposed or amended claim(s) would be al non-allowable claim(s). 	lowable if submitted in a separate,	
7. For purposes of appeal, the proposed amendment(s): a) how the new or amended claims would be rejected is protected. The status of the claim(s) is (or will be) as follows: Claim(s) allowed: Claim(s) objected to: Claim(s) rejected: <u>See Final Rejection mailed April 17, 20</u> Claim(s) withdrawn from consideration:	vided below or appended.	ll be entered and an explanation of
AFFIDAVIT OR OTHER EVIDENCE		
 The affidavit or other evidence filed after a final action, bu because applicant failed to provide a showing of good and was not earlier presented. See 37 CFR 1.116(e). 		
9. The affidavit or other evidence filed after the date of filing entered because the affidavit or other evidence failed to of showing a good and sufficient reasons why it is necessary	overcome <u>all</u> rejections under appea	al and/or appellant fails to provide a
10. ☐ The affidavit or other evidence is entered. An explanatio REQUEST FOR RECONSIDERATION/OTHER	n of the status of the claims after e	ntry is below or attached.
The request for reconsideration has been considered by See Continuation Sheet.	it does NOT place the application in	n condition for allowance because:
12. ☐ Note the attached Information <i>Disclosure Statement</i>(s).13. ☐ Other:	(PTO/SB/08) Paper No(s)	
	/Anh D. Mai/	
	Primary Examiner, Art U	Jnit 2814

Continuation of 11. does NOT place the application in condition for allowance because:

STATUS OF THE CLAIMS:

Claims 7-9, 22 and 23 have been cancelled. The remaining Claims 1, 2 and 4-6 are pending.

FORMAL MATTERS:

Applicant argument With respect to 112 rejection is persuasive. The rejection under 35 U.S.C 112, is withdrawn.

REJECTION UNDER 35 U.S.C 103(a):

With respect to Xiang's 527, Applicant argues: "Applicant respecfully disagree. First, the halo regions disclosed in Xiang et al. are for reducing diffusion of dopants, i.e., transient diffusion that occurs during annealing, from the source and drain regions.".

There are two groups of ions in Xiang can function as "blocking impurity dopant", i.e., neutral: carbon ions and conductive: halo ions. Both of which are implanted into the strained layer 42 including the interface between the strain layer 42 and layer 40. As discussed in the rejection, Xiang does not identify the conductive ions for halo.

However, in view of Noda '802, the conductive dopants for using as halo are well known to include indium (In) or antimony (Sb) for CMOS devices.

Xiang clearly teaches: "halo regions extend beneath the gate 54 to beyond the anticipated locations of the ends of the source and drain extensions 60". (col. 6, lines 1-11). It is well known in the art that "punchthrough" occurs when the S/D extensions are encroached into the channel region. The formation of carbon and halo regions inhibit diffusion of the source and drain into the channel. As has mentioned, both carbon and halo ions are located in the strain layer including the interface.

Therefore, claim 1 is obvious over Xiang and Noda.

The Rejection of claims 1, 2 and 4-6 is maintained.